CLAIMS

1. (Canceled)

2. (Amended) A polishing cloth comprising:

a polishing cloth substrate(1);

a pressure-sensitive adhesive layer(2) laminated on one face of the polishing cloth substrate(1); and

a release sheet(6) attached to the pressure-sensitive adhesive layer(2) in a releasable manner,

characterized in that the pressure-sensitive adhesive layer(2) comprises an adhesive composition containing a polymer, the polymer having a first-order melt transition occurring in a temperature range narrower than 15℃, and the polymer is a side-chain crystallizable polymer, the side-chain crystallizable polymer being comprised in an amount such that the pressure-sensitive adhesive layer(2) becomes substantially untacky to a base of a polishing machine at 20℃ or less and substantially tacky to the base plate of the polishing machine at a temperature higher than 20℃.

3. (Amended) A polishing cloth according to claim 2, characterized in that the side-chain crystallizable polymer comprises as a main component thereof an acrylic acid ester and/or methacrylic acid ester which has a straight-chain alkyl group including 10 or more carbon atoms as a side chain.

4. (Amended) A polishing cloth according to claim 2, characterized in that the side-chain crystallizable polymer is a copolymer of (meth)acrylate having 10 to 14 carbon atoms and at least one monomer selected from the

group consisting of acrylic acid and (meth)acrylate having 1 to 4 carbon atoms.

5. (Amended) A polishing cloth according to claim 4, characterized in that the copolymer comprises the following components:

40 % to 95% by weight of (meth)acrylate having 10 to 14 carbon atoms;

1% to 10% by weight of acrylic acid; and/or

5% to 40% by weight of (meth)acrylate having 1 to 4 carbon atoms.

6. (Amended) A method for attaching/detaching a polishing cloth to/from a base plate of a polishing machine,

the polishing cloth comprising:

a polishing cloth substrate(1);

a pressure-sensitive adhesive layer(2) laminated on one face of the polishing cloth substrate(1); and

a release sheet(6) attached to the pressure-sensitive adhesive layer(2) in a releasable manner,

characterized in that the pressure-sensitive adhesive layer(2) comprises an adhesive composition containing a polymer, the polymer having a first-order melt transition occurring in a temperature range narrower than 15℃, and the polymer is a side-chain crystallizable polymer, the side-chain crystallizable polymer being comprised in an amount such that the pressure-sensitive adhesive layer(2) becomes substantially untacky to a base of a polishing machine at 20℃ or less and substantially tacky to the base plate of the polishing machine at a temperature higher than 20℃, and

characterized in that the method comprises the steps of:

attaching the polishing cloth to the base plate of the polishing machine by removing the release sheet(6) of the polishing cloth from the pressure-sensitive adhesive layer(2), and thereafter allowing the pressure-sensitive adhesive layer(2) of the polishing cloth to adhere to the base plate of the polishing machine while keeping the base plate at a temperature T1; and

after use of the polishing cloth, detaching the polishing cloth from the base plate of the polishing machine while cooling the base plate from the temperature T1 to a temperature T2 , the temperature T2 being lower than the temperature T1.

7. (Amended) A method according to claim 6, characterized in that the temperature T1 is 20℃ or higher, and the temperature T2 is below 20℃.

8. (Amended) A method according to claim 6, characterized in that the temperature T1 is 25℃ or higher, and the temperature T2 is below 20℃.